# Effect of Vacancy on Physical Properties of Cmcm Si<sub>24</sub>

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Researchers recently synthesized a new orthorhombic allotrope of silicon, namely Cmcm Si<sub>24</sub>. This work studied the effect of one vacancy for Cmcm Si<sub>24</sub> on structural, electronic, and mechanical anisotropy properties by the first principle calculation. The lattice parameters of Cmcm Si<sub>24</sub>:V are the same as Cmcm Si<sub>24</sub>, but the density of Cmcm Si<sub>24</sub>:V is larger than that of Cmcm Si<sub>24</sub>. Moreover, the values of elastic moduli for Cmcm Si<sub>24</sub>:V are smaller than for Cmcm Si<sub>24</sub>. The Cmcm Si<sub>24</sub>:V has mechanical stability and anisotropy and has lower formation energy than diamond-Si. The analysis of the band structures shows that Cmcm Si<sub>24</sub> is an indirect band gap material, and the value of the band gap is 1.08 eV. In particular, electronic band structures of Cmcm Si<sub>24</sub>:V exhibit metallic characteristics. Furthermore, the electron localization function indicated strong covalent silicon–silicon bonds in CmcmSi<sub>24</sub> and Cmcm Si<sub>24</sub>:V. In addition, the effective mass of electrons and holes of Cmcm Si<sub>24</sub> is smaller than that of diamond-Si along the *a* direction, and larger than that along the *b* and *c* directions. Finally, the X-ray diffraction patterns for Cmcm Si<sub>24</sub> and Cmcm Si<sub>24</sub>:V are very close after 13.84°.

topics: silicon allotropes, crystal-structure prediction, first-principles method, X-ray diffraction (XRD)

## 1. Introduction

Since the continuous progress of the new energy industry, solar energy, with great potential for development, has been widely discussed [1]. Due to the rapid development of computational materials science, many related materials such as carbon, silicon, germanium, and some metal alloys have been explored [2–6]. For decades, silicon-based photovoltaic devices dominated the solar cell industry due to their great stability, environmentally friendliness, superior efficiency of photoelectric conversion, and technical advantages. Fd-3m-Si (diamond phase) dominates the solar cell market. Nevertheless, Fd-3m-Si has an indirect band gap, and the energy difference between the direct and indirect band gap is up to 2.3 eV, which makes diamond silicon have a lower absorption efficiency. This has limited the application of silicon in the optoelectronics industry to a certain extent [7–9] because the direct band gap materials are able to carry out quick response and high efficiency for optoelectronic devices.

Although more and more researchers are interested in the other allotropes and alloys [10–17], a number of researchers keep searching for silicon allotropes that have direct band gaps or excellent material properties. Through continuous efforts, the researchers predicted a lot of silicon allotropes [18–34]. However, the majority of them still have indirect band gaps. The silicon allotrope, h-Si<sub>6</sub>, which has a 0.61 eV direct band gap, was proposed by Guo et al. [26]. The solar absorption capacity, as well as electron transport characteristics, of  $h-Si_6$  are satisfactory. In addition, Cai et al. [33] predicted a direct band gap allotrope (tP36-Si) with 0.58 eV through first-principles calculation, and its optical performance is superior to diamond-Si. Furthermore, Fan et al. [34] discovered cm-32 silicon and  $P2_1/m$  silicon with a direct band gap. These two silicon allotropes have good photovoltaic efficiency and are suitable for thin-film solar cells. Moreover, He et al. [19] used first-principles calculations to study the stability and physical properties of five  $sp^3$  hybrid silicon allotropes. The results

show that all S-Si, Z-CACB-Si, H-Si, and Z-ACA-Si have quasi-direct band gaps, while M585-Si has a direct band gap of 1.51 eV.

Recently, Kim et al. [35] have synthesized a new orthorhombic silicon allotrope from the removing sodium atom Na<sub>4</sub>Si<sub>24</sub> precursor. They found that the new silicon phase has Cmcm symmetry and Si<sub>24</sub> is a semiconductor material with a 1.3 eV indirect band gap value. Therefore, we studied the effect of vacancy for Si<sub>24</sub> in the Cmcm phase on this basis and used Cmcm Si<sub>24</sub>:V to represent this structure in the following text. The crystal structure and mechanical, and electronic properties of Cmcm Si<sub>24</sub>:V were investigated in this work.

# 2. Computational method

The calculations in this study are implemented by the Cambridge Sequential Total Energy Package (CASTEP) code [36] based on density functional theory (DFT) [37–38]. The generalized gradient approximation (GGA) parameterized by Perdew-Burke–Ernzerhof (PBE) [39] performed exchange and correlation functional. The Broyden-Fletcher-Goldfarb-Shanno (BFGS) [40] minimization optimized the geometry. The interaction between electrons and ions is described by ultrasoft quasipotential [41] in the calculation. Meanwhile, the wave energy cutoff value of Cmcm Si<sub>24</sub> and Cmcm Si<sub>24</sub>:V is 340 eV. In Brillouin zone sampling, the spacing of the k-point Monkhorst–Pack [42] grid is approximately  $2\pi \times 0.025$  Å<sup>-1</sup>. All these ensure good convergence of energy and computational structure in this work. In addition, the elastic moduli, including the bulk, shear, and Young's modulus, are estimated by the Voigt-Reuss-Hill approximation method [43]. Furthermore, the electronic band structures based on Heyd–Scuseria–Ernzerhof (HSE06) hybrid functional [44] are obtained by using the PWmat [45, 46], and the electron localization function (ELF) is studied by using the MedeA VASP [47, 48].

#### 3. Results and discussion

The number of possible crystal structures for Cmcm Si<sub>24</sub>:V is 24, and we then select the most stable possible structure to investigate its physical properties. The crystal structure for Cmcm Si<sub>24</sub> and Cmcm Si<sub>24</sub>:V are shown in Fig. 1. For Cmcm Si<sub>24</sub>, there are three inequivalent silicon atoms that occupy the crystallographic 8f sites, namely 8f (0.00000, 0.24341, 0.55461), 8f (0.00000, 0.57049, 0.34279), and 8f (0.00000, 028753, 0.59015). The red, orange, and pink spheres represent Si1, Si2, and Si3 atoms, respectively. In Fig. 1b, the position of atoms missing for one vacancy is seen clearly. The missing atom position of one vacancy is Si1 (1.00000, 0.24340, 0.55461). Furthermore, the position of the Cmcm Si<sub>24</sub>:V is consistent with previous



Fig. 1. The crystal structures of Cmcm Si<sub>24</sub> (a) and Cmcm Si<sub>24</sub>:V (b).

TABLE I

The density  $[g/cm^3]$  and lattice parameters [Å] for Cmcm Si<sub>24</sub> and Cmcm Si<sub>24</sub>:V.

Material	Method	$\rho$	a	b	c	Ref.
$Si_{24}$	PBE	1.714	3.858	10.762	12.789	this work
			3.848	10.744	12.734	[35]
			3.822	10.701	12.626	exper. [35]
$\mathrm{Si}_{24}:V$	PBE	2.020	3.848	10.477	12.814	this work

report [49]. The lattice parameters and density for Cmcm Si<sub>24</sub> and Cmcm Si<sub>24</sub>:V are listed in Table I (see also [35]), along with the calculated theoretical values and experimental values for Cmcm Si<sub>24</sub>. The lattice parameters of Cmcm Si<sub>24</sub> are in compliance with the experimental values [35] in Table I, demonstrating the credibility of the theoretical results obtained in this work. As seen in Table I, the lattice parameters a and b of Cmcm Si<sub>24</sub>:V are smaller than those of Cmcm Si<sub>24</sub>, while c of Cmcm Si<sub>24</sub>:V is larger. The results show that the presence of vacancy changes the lattice parameters and density of Cmcm Si<sub>24</sub>:V is larger than that of Cmcm Si<sub>24</sub>.

The elastic constants, bulk modulus B, shear modulus G, and Young's modulus E for Cmcm Si<sub>24</sub> and Cmcm Si<sub>24</sub>:V are also researched in the paper, and the results are listed in Table II. There are nine independent elastic constants for orthorhombic crystal, namely  $C_{11}$ ,  $C_{12}$ ,  $C_{13}$ ,  $C_{22}$ ,  $C_{23}$ ,  $C_{33}$ ,  $C_{44}$ ,  $C_{55}$ , and  $C_{66}$ . Therefore, the stable structure for an orthorhombic system should meet the following necessary and sufficient Born's mechanical

The elastic constants [GPa] and elastic modulus [GPa] for Cmcm Si<sub>24</sub> and Cmcm Si<sub>24</sub>:V.

#### TABLE II

	C <sub>11</sub>	$C_{12}$	$C_{13}$	$C_{22}$	$C_{23}$	C <sub>33</sub>	$C_{44}$	$C_{55}$	$C_{66}$	В	G	E
Si <sub>24</sub>	162	32	33	189	39	140	46	48	53	77	54	132
$Si_{24}:V$	136	31	32	146	35	110	33	45	30	65	40	99

stability criteria:  $C_{11} > 0$ ,  $C_{11}C_{22} > C_{12}^2$ ,  $C_{11}C_{22}C_{33} + 2C_{12}C_{13}C_{23} - C_{11}C_{23}^2 - C_{22}C_{13}^2C_{33}C_{12}^2 > 0$ ,  $C_{44} > 0$ ,  $C_{55} > 0$ ,  $C_{66} > 0$  [50]. Obviously, the independent elastic constants for Cmcm Si<sub>24</sub> and Cmcm Si<sub>24</sub>:V in Table II satisfy the orthorhombic symmetry generalized Born's mechanical stability criteria. This demonstrates the mechanical stability of Cmcm Si<sub>24</sub> and Cmcm Si<sub>24</sub>:V.

To determine whether the native defects are easily formed in Cmcm Si<sub>24</sub>, the calculation of formation energy and defect formation energy is imperative. The formation energy ( $\Delta E$ ) for Cmcm Si<sub>24</sub> and Cmcm Si<sub>24</sub>:V is defined as

$$\Delta E = E_{Cmcm\,\text{phase}}/m - E_{\text{diamond phase}}/n, \quad (1)$$

where  $E_{Cmcm \text{ phase}}$  is the total energy of the crystals at equilibrium lattice constant;  $E_{\text{diamond phase}}$  is the energy of diamond Si; *m* represents the number of atoms in the conventional cell of the *Cmcm* phase, so it is equal to 24 and 23, respectively; *n* is equal to 8. The definition of defect formation energy is

$$\Delta E_f = E_{\text{defect}} - E_{perfect} + \sum_i n_i \mu_i, \qquad (2)$$

where  $E_{defect}$  is the total energy of defective supercell;  $E_{perfect}$  is the total energy of perfect intrinsic supercell;  $n_i$  represents the number of atoms (i) removed from  $(n_i > 0)$  or added to  $(n_i < 0)$  the perfect supercell, and  $\mu_i$  represents the chemical potential of the corresponding atom.

Table III (see also [51]) listed the results of formation energy and defect formation energy for Cmcm  $Si_{24}$ , diamond-Si:V, and  $Cmcm Si_{24}:V$ . The formation energy  $\Delta E$  of Cmcm Si<sub>24</sub>, Cmcm Si<sub>24</sub>:V, and diamond-Si:V are 0.089, 0.217, and 0.417 eV/atom, respectively. The defect formation energy  $\Delta E_f$  of Cmcm Si<sub>24</sub>:V and diamond-Si:V are 4.315 and 4.438 eV. For diamond-Si:V, the calculated  $\Delta E_f$ is 4.438 eV, which is not significantly different from the 4.01 eV value proposed in previous literature [51], which proves the accuracy and effectiveness of our calculation. Actually, we all know that it is easier to form low-energy structures. As shown in Table III, the defect formation energy of diamond-Si:V is similar to that of Cmcm Si<sub>24</sub>:V. However, the formation energy of Cmcm Si<sub>24</sub>:V is much lower than the formation energy for diamond-Si:V; this illustrates the synthesized possibility for vacancy in the Cmcm Si<sub>24</sub>.

The bulk modulus and shear modulus are estimated according to the obtained elastic constants, and Young's modulus is estimated from the value of bulk modulus and shear modulus



Fig. 2. The three-dimensional directional dependence of Young's modulus for Cmcm Si<sub>24</sub> (a) and Cmcm Si<sub>24</sub>:V (b).

#### TABLE III

The formation energies and defect formation energies for Cmcm Si<sub>24</sub>, diamond-Si:V, and Cmcm Si<sub>24</sub>:V.

	Vacancy	$\Delta E$	$\Delta E_f$	Rof	
	vacancy	[eV/atom]	[eV]	1001.	
$Si_{24}$	zero	0.089		this work	
	one	0.217	4.315	this work	
diamond-Si	one	0.417	4.348	this work	
diamond-Si	one		4.01	[51]	

by E = 9BG/(3B + G) [43]. As shown in Table II, the presence of vacancy changes the elastic moduli of *Cmcm* Si<sub>24</sub>, and the values of *B*, *G*, and *E* for *Cmcm* Si<sub>24</sub>:V are all smaller than for *Cmcm* Si<sub>24</sub>. The bulk modulus of *Cmcm* Si<sub>24</sub> is 77 GPa, the shear modulus is 54 GPa, and the Young's modulus is 132 GPa. Moreover, the *B*, *G*, and *E* values of *Cmcm* Si<sub>24</sub>:V are 65, 40, and 99 GPa, respectively. For the purpose of further study of the influence of vacancy on the anisotropy of elastic modulus of structure, the three-dimensional (3D) surface constructions of Young's modulus are investigated

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Fig. 3. The band structures of Cmcm Si<sub>24</sub> (a), Cmcm Si<sub>24</sub>:V in one cell (b), Cmcm Si<sub>24</sub>:V in  $1 \times 1 \times 3$  supercell (c), and the Brillouin zone for Cmcm Si<sub>24</sub> and Cmcm Si<sub>24</sub>:V (d).

in this work. Figure 2 shows the 3D directional dependence of Young's modulus for Cmcm Si<sub>24</sub> and Cmcm Si<sub>24</sub>:V. The 3D figure of an isotropic structure exhibits a spherical shape, while the anisotropy degree is represented by deviation from the spherical shape. The deformed spheres plotted in Fig. 2 show that Cmcm Si<sub>24</sub> and Cmcm Si<sub>24</sub>:V have mechanical anisotropy, and the anisotropy of Cmcm Si<sub>24</sub>:V is greater than Cmcm Si<sub>24</sub>.

Since band structures are able to depict the electronic properties of crystals, in this work, the electronic band structures are investigated by using the HSE06 function and PWmat. Figure 3 displays the band structures and Brillouin zone for Cmcm Si<sub>24</sub> and Cmcm Si<sub>24</sub>:V. Figure 3d shows the Brillouin zone of  $Si_{24}$ ; the coordinates of high symmetry points across the Brillouin zone for Cmcm  $Si_{24}$  and Cmcm  $Si_{24}$ :V are G (0.0, 0.0, 0.0)  $\rightarrow$  $\mathbf{S}$ (-0.5, 0.0, 0.0) $\rightarrow$ Y (-0.5, 0.5, 0.0) $\rightarrow$  $\mathbf{G}$ (0.0, 0.0, 0.0) $\rightarrow$ Х (0.0, 0.5, 0.0) $\rightarrow$ U (0.0, 0.5, 0.5) $\rightarrow$ G (0.0, 0.0, 0.0) $\rightarrow$ Ζ (0.0, 0.0, 0.5) $\rightarrow$ R (-0.5, 0.0, 0.5) $\rightarrow$ Т (-0.5, 0.5, 0.5) $\rightarrow$  G (0.0, 0.0, 0.0). As can be seen in Fig. 3a, Cmcm Si<sub>24</sub> is a semiconductor material with an indirect band gap of 1.08 eV, the conduction band minimum (CBM) of Cmcm Si<sub>24</sub> is between the G point and the X point, while the valence band maximum (VBM) is located at the G point. Compared with Cmcm Si<sub>24</sub>, the presence of vacancy has a great impact on electronic band structures. In particular, the Cmcm Si<sub>24</sub>:V exhibits metallic characteristics in electronic band structures. VBM for Cmcm Si<sub>24</sub>:V is located at the Z point, while its conduction bands along G-S-Y-G and Z–G directions exhibit metallic characteristics since the bottom dispersive band crosses into the region below Fermi level with negative energy. In order to avoid the problem of band anomalies caused by high defect concentration, we conducted band calculations on supercells that expand three times along the direction a in Fig. 1, as shown in Fig. 3c. We found that the band gap of the band structure in Fig. 3c is indeed narrower than that in Fig. 3b, but both band structures exhibit metallic properties. To further illustrate the chemical bonding in Cmcm Si<sub>24</sub> and Cmcm Si<sub>24</sub>:V, the electron localization function (ELF) using an isosurface value of 0.8 are exhibited in Fig. 4. The high ELF values with symmetric shapes at the bond centers indicated strong covalent silicon-silicon bonds.

Effective mass is one of the important indicators for grading the transport performance of semiconductors, and it is in a position to provide a theoretical basis for the crystal orientation design of semiconductor devices by analysis of its anisotropy. The effective masses of Cmcm Si<sub>24</sub> are calculated by using the relation

$$\frac{1}{m^*} = \frac{1}{\hbar^2} \frac{\partial^2 E}{\partial k^2}.$$
(3)

The effective masses of holes and electrons for diamond-Si and Cmcm Si<sub>24</sub> along the a, b, and c axes are given in Table IV (see also [48, 49]).

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Material	Electron effective mass			Н	Bof			
	a direction	b direction	c direction	a direction	b direction	c direction	itei.	
diamond-Si .	0.016	0.191	0.191	0.460 (heavy)	0.460 (heavy)	0.460 (heavy)	exper. [48, 49]	
	0.910			0.171 (light)	0.171 (light)	0.171 (light)		
	0.926	0.195	0.195	0.268 (heavy)	0.268 (heavy)	0.268 (heavy)	this work	
				0.178 (light)	0.178 (light)	0.178 (light)	this work	
$Si_{24}$	0.129	0.608	1.344	0.136	0.465	2.004	this work	

Effective masses of holes and electrons (in  $m_0$ ) for diamond-Si and Cmcm Si<sub>24</sub> along the a, b, and c directions.



Fig. 4. ELF for Cmcm Si<sub>24</sub> (a) and Cmcm Si<sub>24</sub>:V (b) with an isosurface level set to 0.8.

The calculated effective mass of diamond-Si is consistent with the reported experimental results, proving the reliability of our research results. The effective mass of electrons and holes of Cmcm Si<sub>24</sub> is smaller than diamond-Si along the *a* direction and larger than that along the *b* and *c* directions. In order to analyze the anisotropy and directionality of material effective mass more directly, we plotted the three-dimensional (3D) representation diagram of effective mass in Fig. 5. The 3D shapes of the electrons and holes effective mass of CmcmSi<sub>24</sub> are tall and slender. These results indicated the greater anisotropy of the effective mass of electrons and holes of Cmcm Si<sub>24</sub> than that of diamond-Si.



Fig. 5. Three-dimensional contour plots of the effective masses (in  $m_0$ ) of electrons (a) and holes (b) of *Cmcm* Si<sub>24</sub>.

An X-ray wavelength of 1.5406 Å and a copper source are used in this work to simulate the X-ray diffraction (XRD) patterns. The XRD patterns for Cmcm Si<sub>24</sub> and Cmcm Si<sub>24</sub>:V are displayed in Fig. 6. It can be seen from the diffraction peaks after  $13.84^{\circ}$  that the XRD spectra for Cmcm Si<sub>24</sub> and Cmcm Si<sub>24</sub>:V are very close. There are many diffraction peaks in XRD patterns of Cmcm Si<sub>24</sub>, and several peaks of the main diffraction peaks marked in the figure are (002), (020), (021), (022), and (113). The (002), (020), (021), and(022) peaks are located at the diffraction angles of  $13.84^{\circ}, 16.46^{\circ}, 17.87^{\circ}, \text{ and } 21.57^{\circ}, \text{ respectively. The}$ (113) peak is located around  $32.35^{\circ}$ , and the diffraction angles of  $47.05^{\circ}$  has the (200) peak. Compared with Cmcm Si<sub>24</sub>, the XRD patterns before  $13.84^{\circ}$  of Cmcm Si<sub>24</sub>:V has four diffraction peaks,



Fig. 6. Simulated XRD patterns for Cmcm Si<sub>24</sub> and Cmcm Si<sub>24</sub>:V; X-ray wavelength of 1.5406 Å and a copper source were used for simulation in this work.

namely (001), (010), (011), and (01-1), which appear at the diffraction angles of  $6.91^{\circ}$ ,  $8.21^{\circ}$ , and  $10.73^{\circ}$ , respectively. It also has the major diffraction peaks of (002), (020), (021), (022), and (113) at the diffraction angles of  $13.84^{\circ}$ ,  $16.46^{\circ}$ ,  $17.87^{\circ}$ , and  $21.57^{\circ}$ . The difference is that when the diffraction angle is  $32.35^{\circ}$ , four diffraction peaks simultaneously appear in the XRD patterns of *Cmcm* Si<sub>24</sub>:V. They are (1-1-3), (1-13), (113), and (11-3) peaks, respectively. These X-ray diffraction characteristics are of great significance and provide guidance for analyzing the structure of *Cmcm* Si<sub>24</sub> and *Cmcm* Si<sub>24</sub>:V in subsequent experiments.

# 4. Conclusions

In general, this work utilized the first principle calculation based on density functional theory to investigate the effect of the presence of Cmcm Si<sub>24</sub>:V on physical properties. The results show that the presence of vacancy does not affect the crystal lattice parameters, but the density of Cmcm Si<sub>24</sub>:V is larger than Cmcm Si<sub>24</sub>. The elastic constants satisfied the orthorhombic symmetry generalized Born's mechanical stability criteria and demonstrated the mechanical stability for Cmcm  $Si_{24}$  and  $Cmcm Si_{24}$ :V. The lower formation energy of Cmcm Si<sub>24</sub>:V illustrated the synthesized possibility. Moreover, 3D surface constructions of Young's modulus of Cmcm Si<sub>24</sub> and Cmcm Si<sub>24</sub>:V show that they have varying degrees of mechanical anisotropy. According to the electronic band structures, Cmcm Si<sub>24</sub> has indirect band gaps of 1.08 eV. Furthermore, the Cmcm Si<sub>24</sub>:V exhibits metallic characteristics in electronic band structures. These results indicated that the presence of vacancy of Cmcm Si<sub>24</sub> has a great effect on electronic band structure. In addition, the high ELF values with symmetric shapes at the bond centers indicated strong covalent silicon–silicon bonds of the vacancy structure of Cmcm Si<sub>24</sub>. The effective mass of electrons and holes of Cmcm Si<sub>24</sub> is smaller than that of diamond-Si along the *a* direction and larger than that along the *b* and *c* directions. Finally, this work studied the X-ray diffraction characteristics for Cmcm Si<sub>24</sub> and Cmcm Si<sub>24</sub>:V, which has important guiding significance for the analysis in subsequent experiments. The XRD patterns for Cmcm Si<sub>24</sub> and Cmcm Si<sub>24</sub>:V are very close after 13.84°.

The data that support the findings of this study are available from the corresponding author upon reasonable request.

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